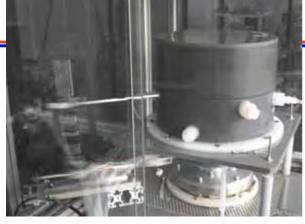
概要

Overview

プロセス

システム



## AccuZone -ZC2

Photomask Resist Strip/Clean System

## Application – Ozone and Hot-DI Wet Strip and Clean System

*In Brief:* Ozone gas in combination with heated DI water provides an alternative photoresist removal and surface clean chemistry to traditional SPM-based methods. Atomic oxygen released on decomposition of  $O_3$  into  $O_2$  + O rapidly attacks organics (C-H bonds) and the reaction byproducts are hydrolized and dissolved in hot DI water



Partially-stripped plate



AccuZone-stripped plate

## **Features and Benefits**

Feature	Benefit
Ozone gas and DIW	Sulfate-free processing for Resist Strip and Clean eliminates
chemistry	Sulfate-residue haze formation
	Avoids neutralization/abatement of hazardous waste stream
	Eliminate wet-chemical mixing and supply modules
Heated DIW	Enhances reaction rate for faster strip, better particle removal
Integration	Fully Compatible standard MTC module, plus separate (remote-sited)
	O <sub>3</sub> generator unit
Built-in ozone abatement	In-line treatment of liquid and exhaust streams within sealed system
	enclosure

